Application No. 10/807,280

## Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method of manufacturing a thin-film magnetic head, the method comprising the steps of:

forming a first magnetic pole layer;

removing both sides in a track width direction of the first magnetic pole layer so as to leave a predetermined residual area in the first magnetic pole layer;

forming an insulating layer about the residual area of the first magnetic pole layer;

forming a gap layer made of a nonmagnetic material on the residual area of the first magnetic pole layer and the insulating layer;

forming on the gap layer a second magnetic pole layer magnetically connected to the first magnetic pole <u>layer</u>; and

patterning the second magnetic pole layer by etching while using a mask, so that a width of the second magnetic pole layer in the track width direction is smaller than that of the residual area.

- 2. (Original) A method of manufacturing a thin-film magnetic head according to claim 1, wherein the insulating layer is formed from Al<sub>2</sub>O<sub>3</sub>.
- 3. (Original) A method of manufacturing a thin-film magnetic head according to claim 1, wherein the residual area of the first magnetic pole layer has a width of about 0.5  $\mu$ m to about 2.0  $\mu$ m in the track width direction.
- 4. (Original) A method of manufacturing a thin-film magnetic head according to claim 1, wherein the first magnetic pole layer is constructed by laminating a plurality of magnetic layers;

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wherein at least the topmost layer in the plurality of magnetic layers is formed with the residual area; and

wherein the insulating layer is formed on both sides in the track width direction of the residual area.

